



SUBTLE

SUB KT LOW ENERGY TRANSISTORS AND SENSORS



Noise enhanced sensing and switching with nanoelectronic devices

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Contract Number: IST-034236

Project duration: October 1, 2006 to September 30, 2009

No	Participating Institution	Nick Name	Country
1	Bayerische Julius Maximilians Universität Würzburg	UWUERZ	Germany
2	Technical Research Centre of Finland	VTT	Finland
3	Lund University	LU	Sweden
4	University of Geneva	UNIGE	Switzerland
5	Dipartimento di Fisica Università degli Studi Perugia	UNIPG	Italy
6	XENOS Semiconductors Technologies GmbH	XENOS	Germany



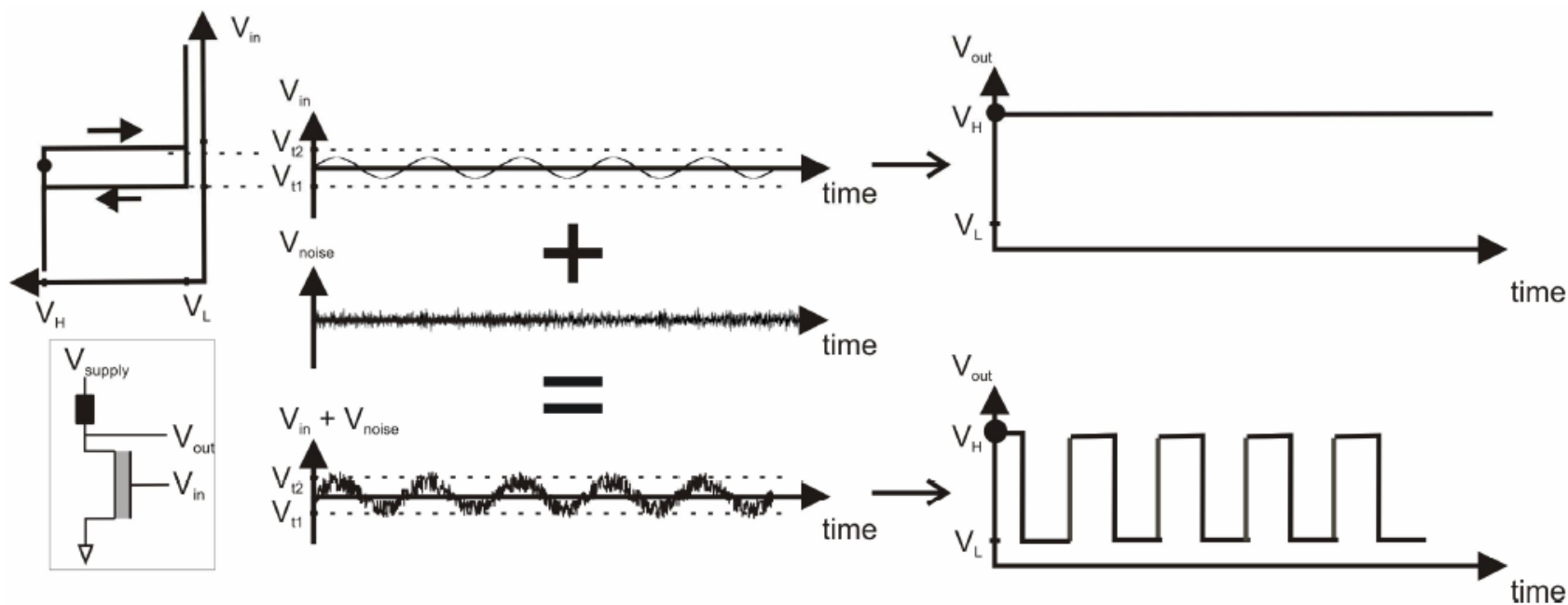
LUNDS
UNIVERSITET



Università degli Studi di Perugia
 Dipartimento di Fisica



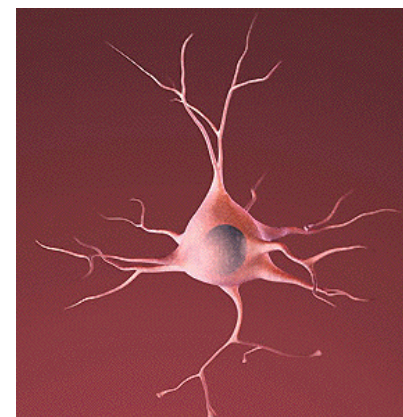
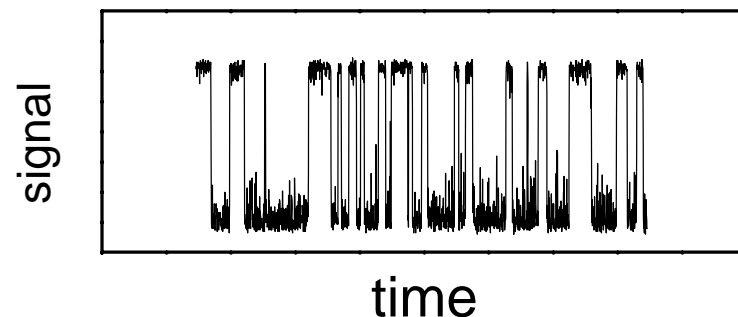
- Major idea: exploitation of stochastic-resonance (SR) phenomena in nanoelectronics



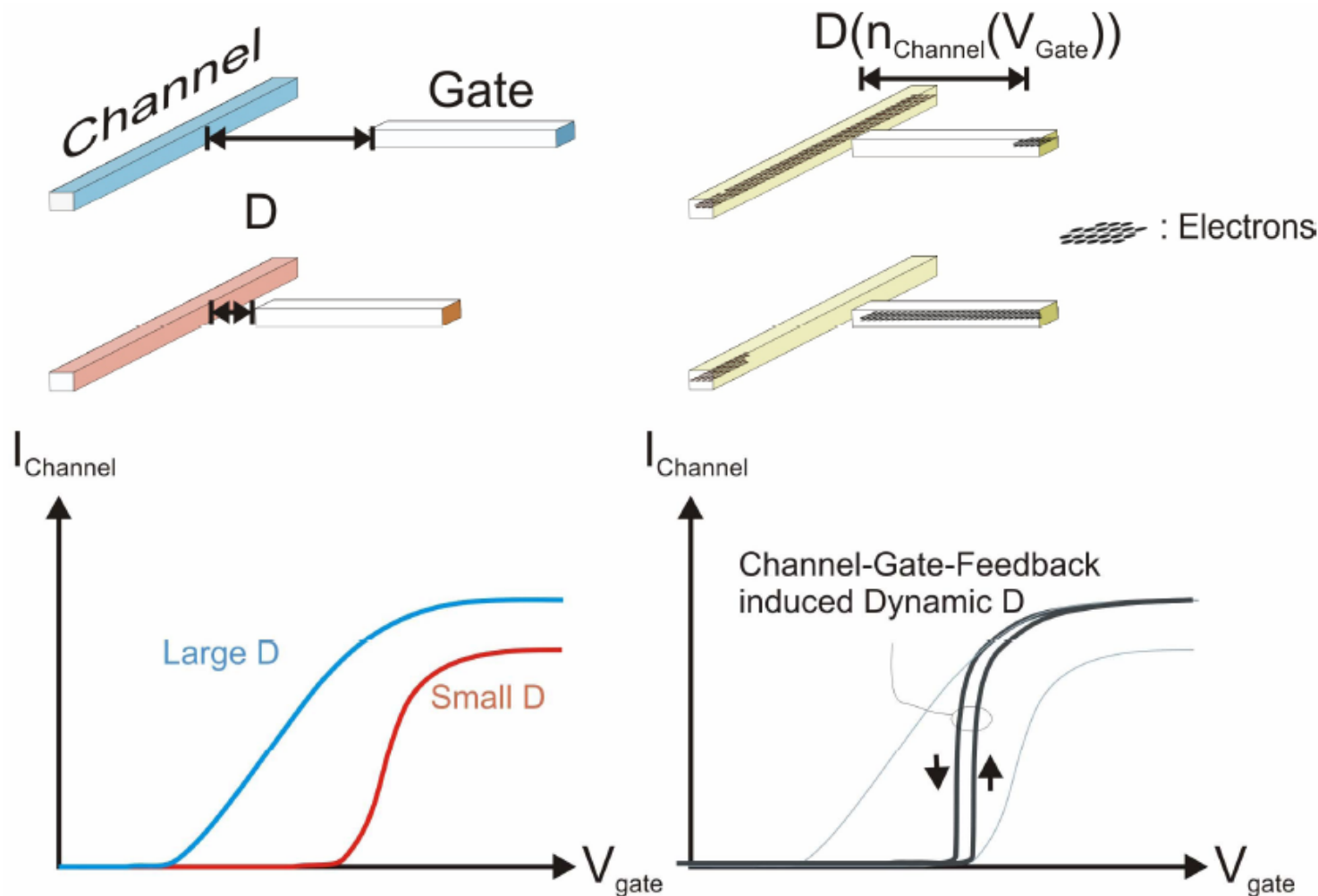
- Nanoelectronic devices with **key properties**:
 - Subthermal signal resolution
 - Noise activated switching
 - Noise enhanced signal processing

- Stochastic-Resonance-related phenomena due to
 - Back-action between gate and channel }
 - Noise
 - External
 - Intrinsic
- Feedback between low-dimensional conductors
 - Lateral
 - Vertical
- Sensing and switching
 - Subthermal resolution
 - Asymmetry due to non linear transport: magnetic & electric
 - Artificial neuron nodes

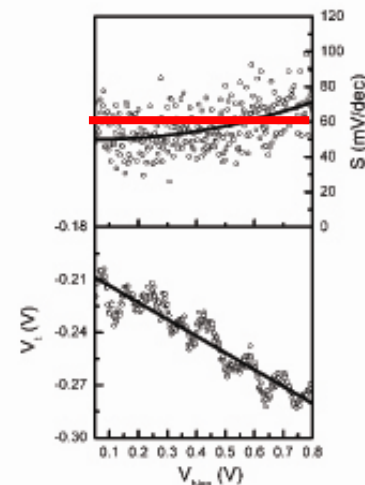
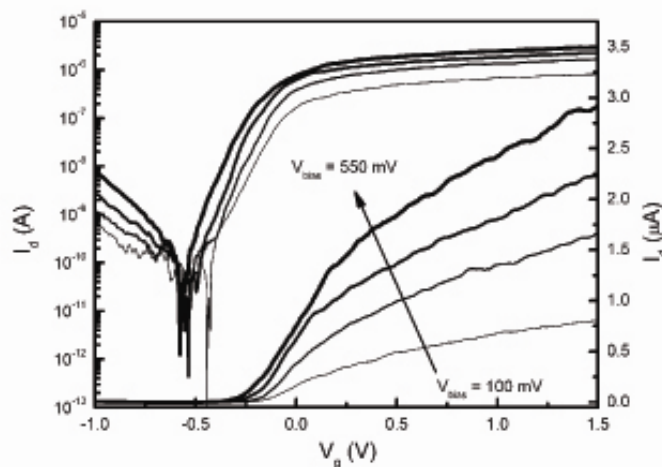
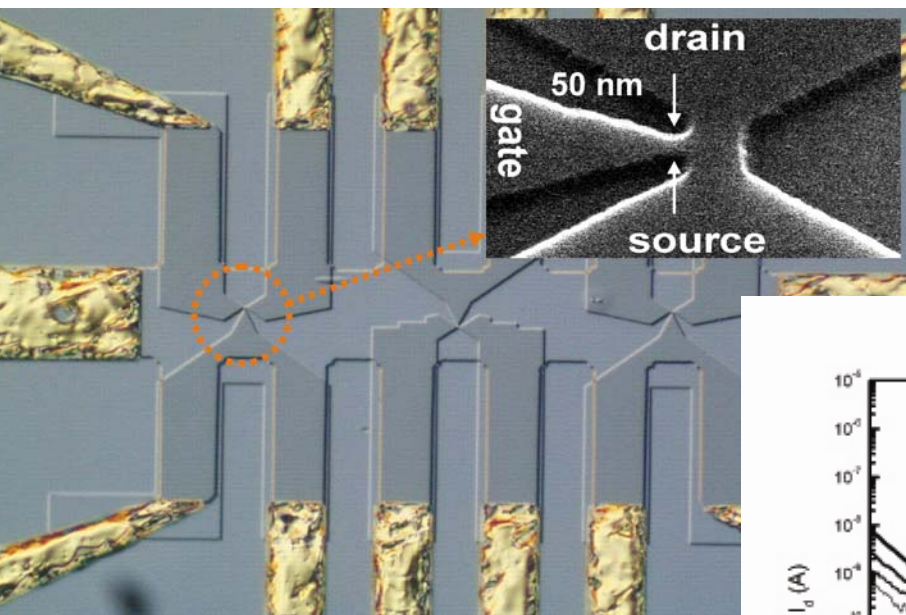
usually one tries to avoid these features



- Nanoelectronic devices with nonlinear dynamic characteristics for noise enhanced functioning
 - Steep threshold, bistable switching, noise

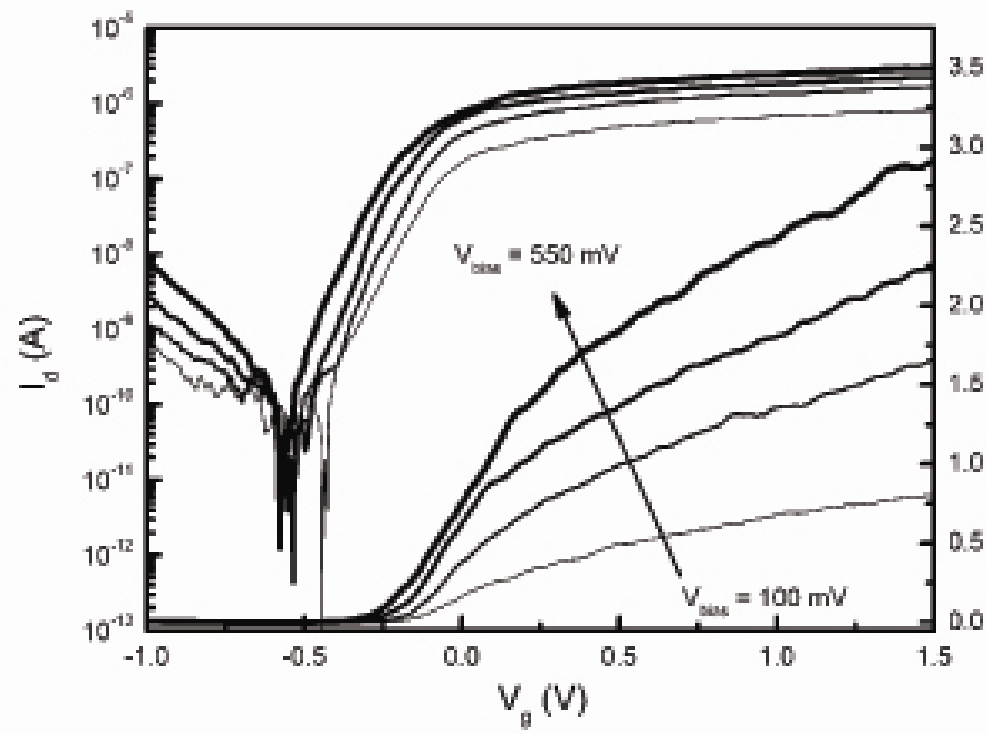


Three-terminal junction TTJ : low-dimensional gate

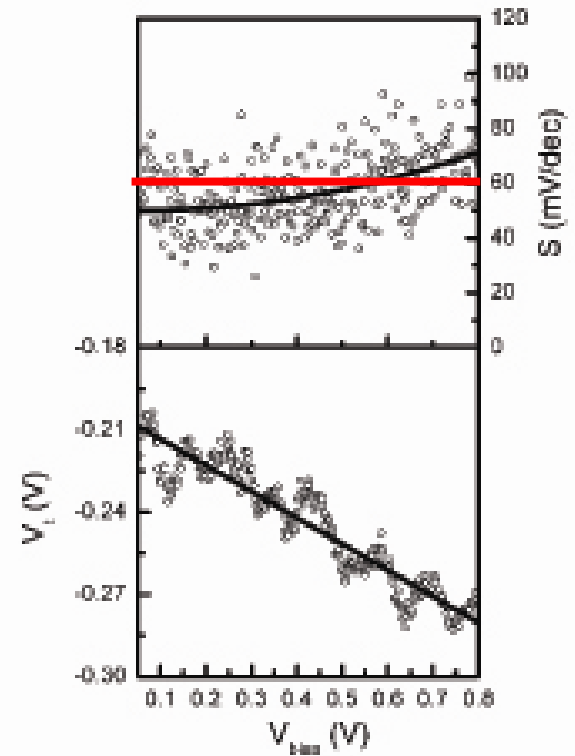


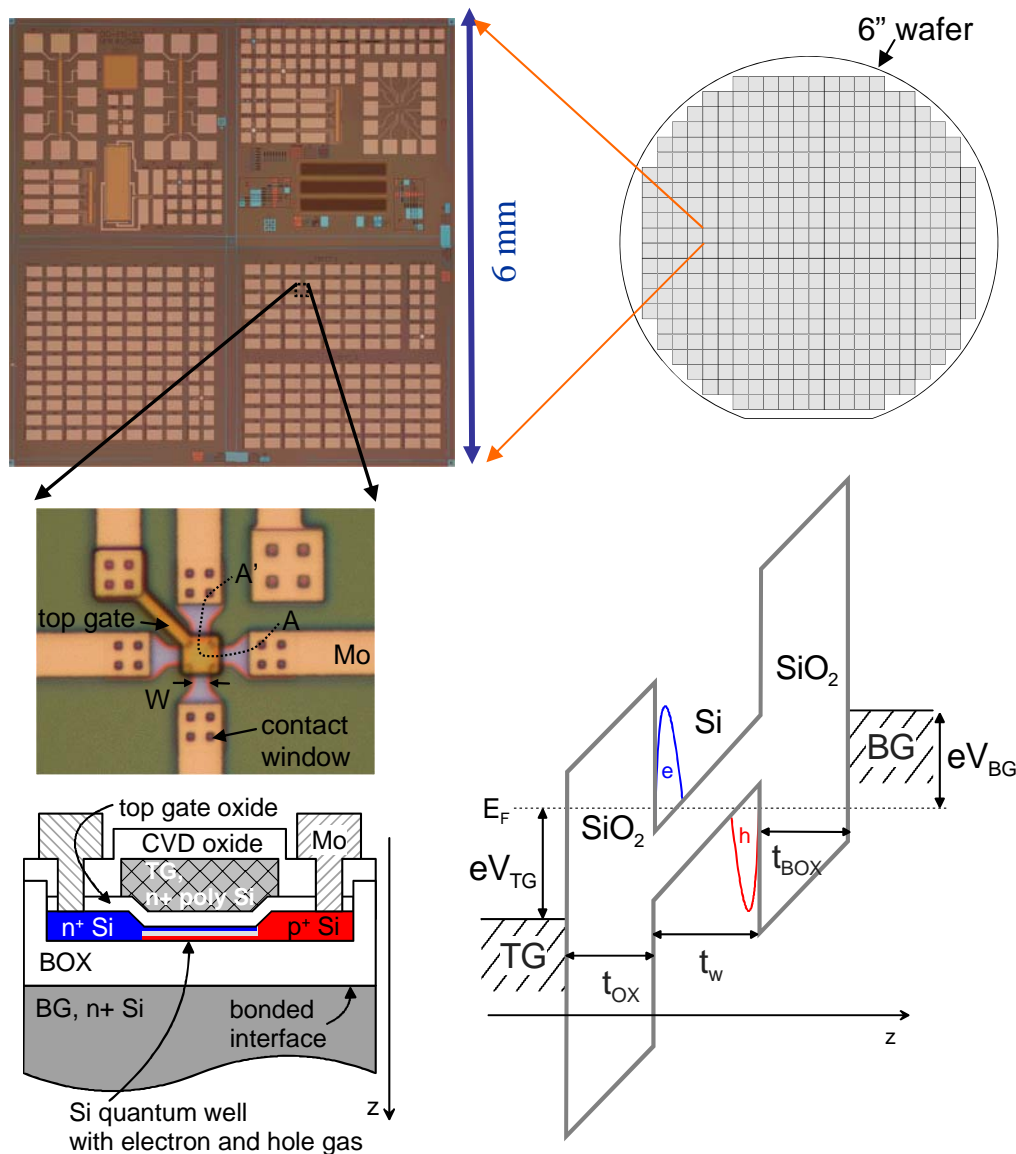
GaAs based HEMT → TTJ by ebeam lithography + lift-off
 Microscope image of a monolithically integrated triple TTJ device
 Monolithic gate: dimension smaller than channel

Transfer characteristics of a TTJ

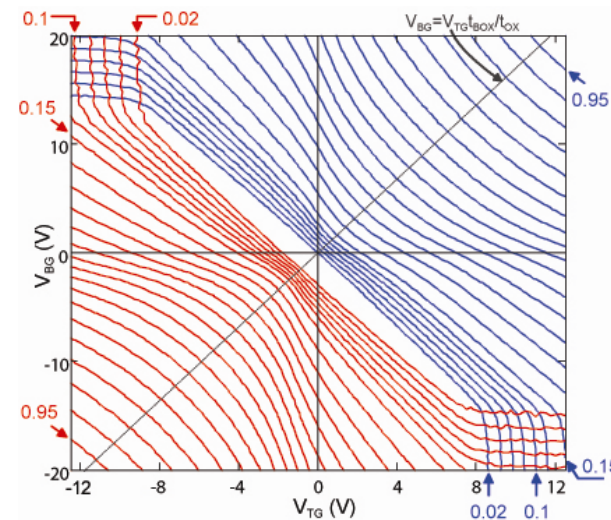


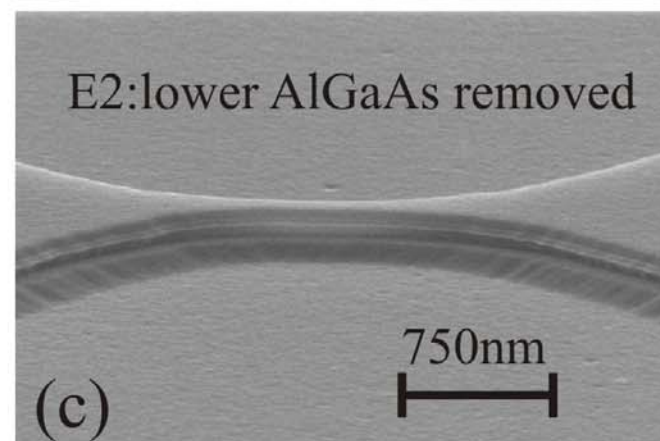
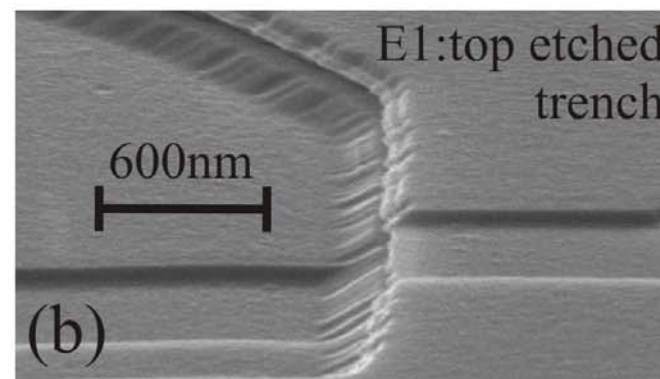
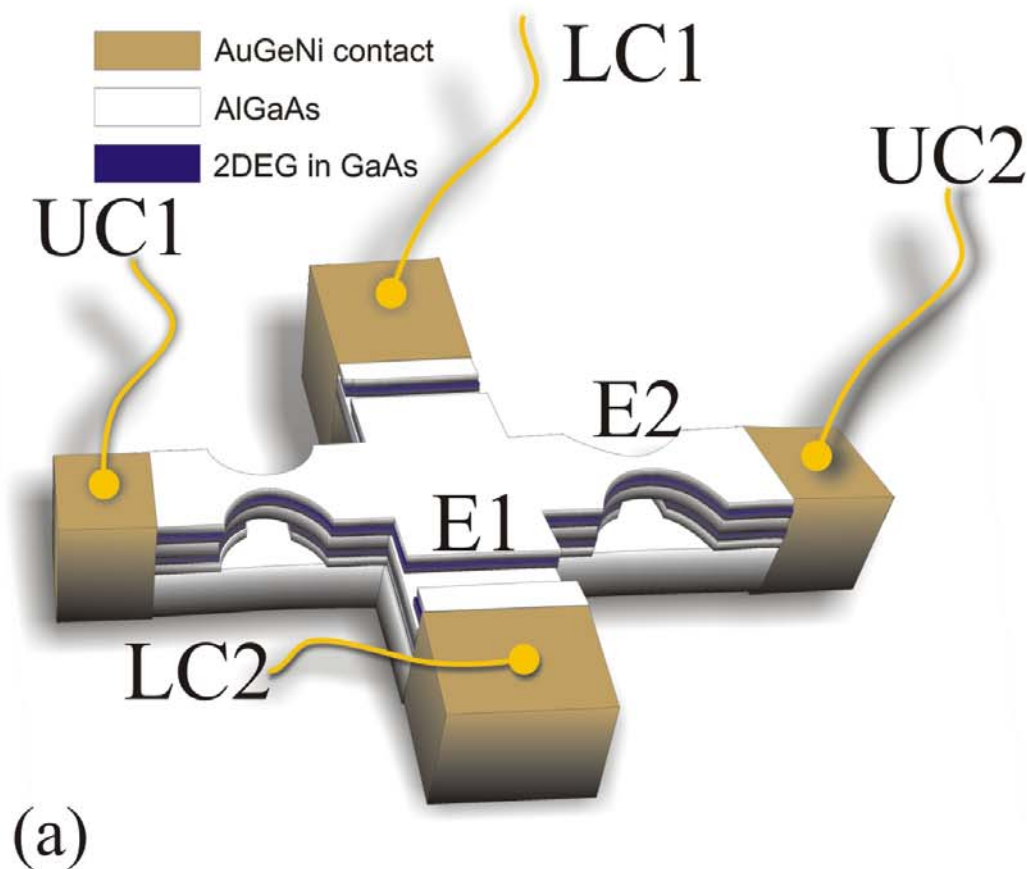
Sub-threshold swing smaller than 60mV @ RT and threshold voltage





- Design and first successful fabrication of a 9-layer CMOS-based fabrication process for Si electron-hole bilayer devices and RT drag resistance



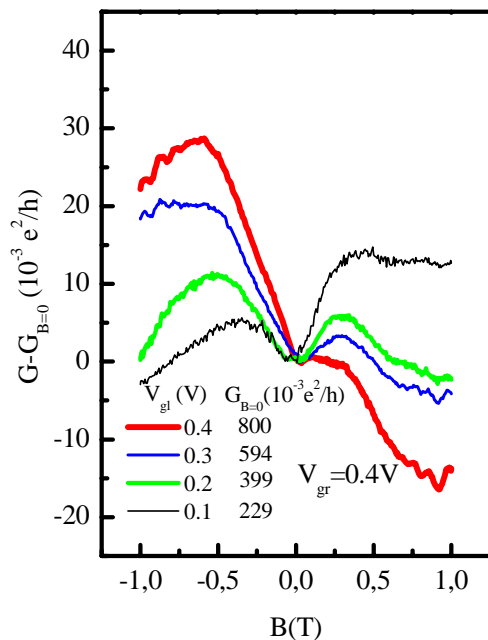


- Variation of Al content using two Al sources
- Selective etching
- FET operation with efficient gating

Key devices

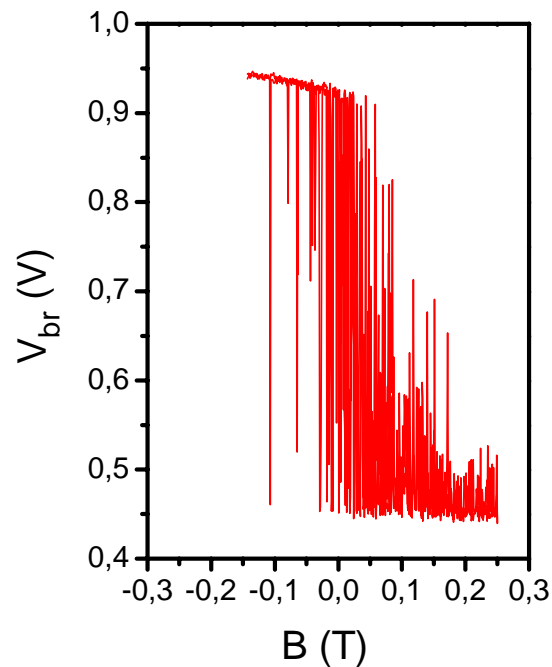
- Electrochemical capacitance induced feedback transistors (**FBFETs**)
- Noise activated nonlinear devices (**NADS**)
- Noise enhanced signal processing nodes (**NENS**)

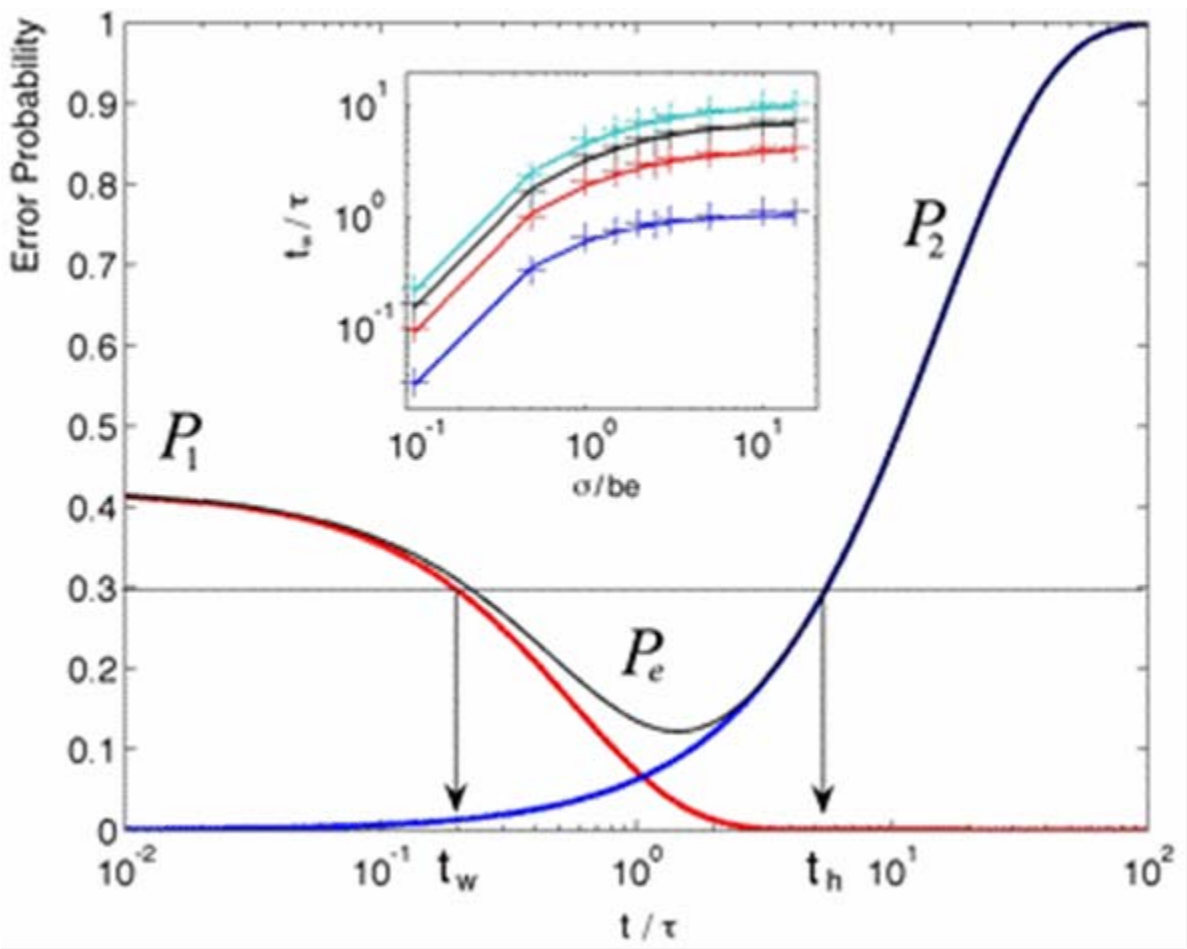
Asymmetry of nonlinear mesoscopic transport in a quantum wire



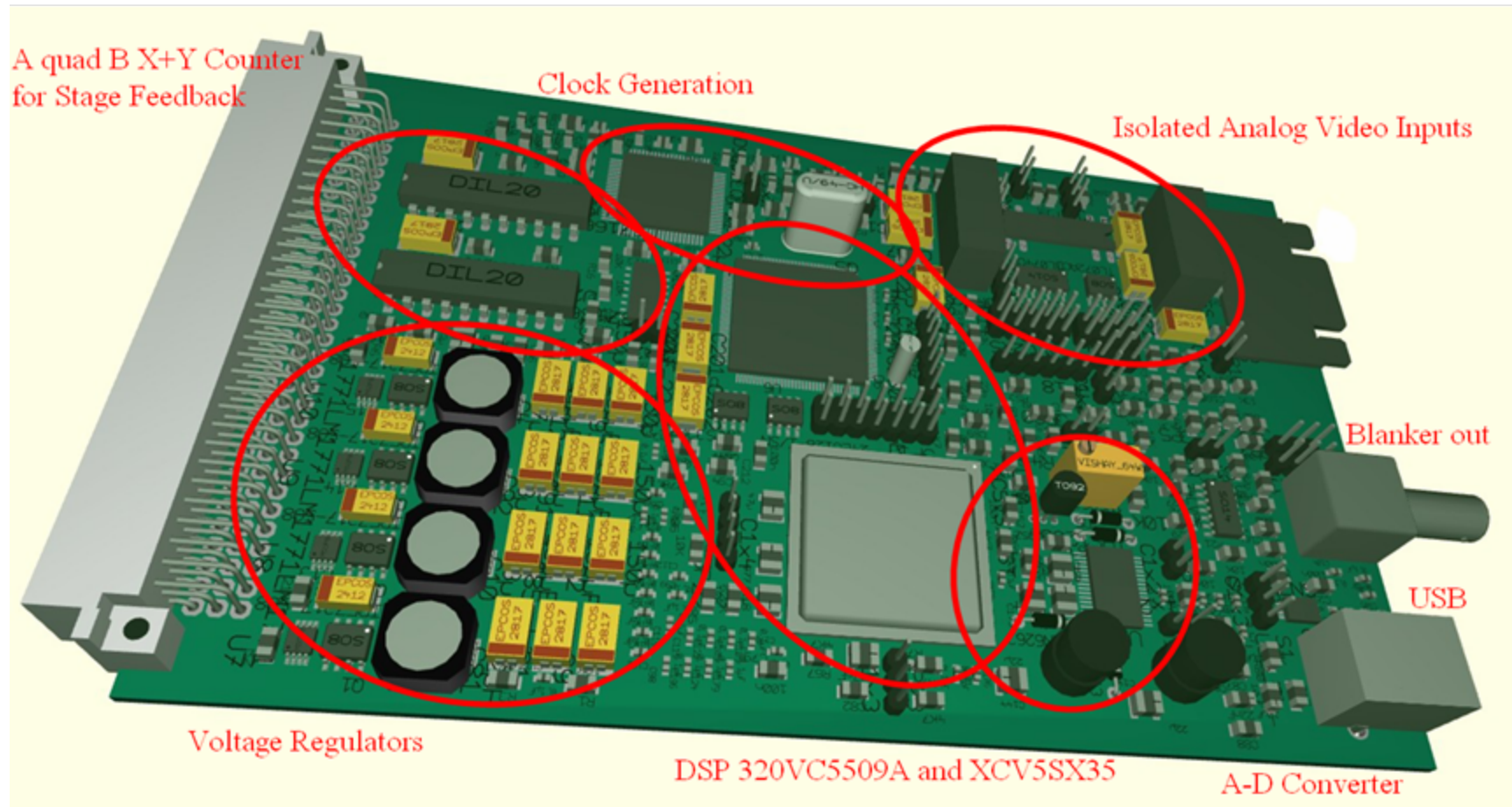
+ noise

Exploited in a **NAD** as magnetic field detector





- The presence of the noise sets a fundamental limit to the computing speed.
- We found an optimal *idle time* interval that minimizes the error probability.



- Architectural design of 150 MHz pattern controller

Theory

- Models were developed for description of manybody effects in electro-chemical capacitance describing the role of dephasing and thermal averaging on the charge relaxation
- First simulation results of Stochastic Resonance and residence time variations in NADs
- Modeling of noise limited computational speed

Experiment-Applications

- Observation of field-effect controlled magnetic field asymmetry in nonlinear mesoscopic transport
- Independent contacts to GaAs quantum wells (QWs) in a double QW structure separated less than 10 nm on the basis of nanofabrication techniques and selective etching
- Design and first successful fabrication of a 9-layer CMOS-based fabrication process for Si electron-hole bilayer devices
- Development of double-dot FET InGaAs/InP with HfO ALD isolation
- Three-terminal junction (TTJ) FET with subthreshold swing smaller than $kT \ln 10$
- First prototype (NADS) for nanoscale magnetic field sensor

